

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	223	((insulat\$3 dielectric) (zircona (zirconium near3 (oxide dioxide)) (ZrO2 "ZrO.sub."\$2)) hafna (hafnium near5 (oxide dioxide)) (HfO2 "HfO.sub."\$2)) same (implant\$3 dop\$3 treat\$3) same (amorphous amorphiz\$4) same (etch\$3 pattern\$3)).clm.	US-PGPU B	OR	ON	2005/10/20 18:59
L3	184	((insulat\$3 dielectric) (zircona (zirconium near3 (oxide dioxide)) (ZrO2 "ZrO.sub."\$2)) hafna (hafnium near5 (oxide dioxide)) (HfO2 "HfO.sub."\$2)) same (implant\$3 dop\$3 treat\$3) same (amorphous amorphiz\$4) same gate same (etch\$3 pattern\$3)).clm.	US-PGPU B	OR	ON	2005/10/20 18:59